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APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.	
10/621,712	07/17/2003	Qi Wang	NREL 02-34	1540	
23712	7590 05/30/2006		EXAM	INER	
	ITE, SENIOR COUN	GHYKA, ALE	GHYKA, ALEXANDER G		
NATIONAL RENEWABLE ENERGY LABORATORY (NREL) 1617 COLE BOULEVARD		ART UNIT	PAPER NUMBER		
GOLDEN, CO	0 80401-3393		2812	2812	

DATE MAILED: 05/30/2006

Please find below and/or attached an Office communication concerning this application or proceeding.

		Application No.	Applicant(s)			
Office Action Summary		10/621,712	WANG, QI			
		Examiner	Art Unit			
		Alexander G. Ghyka	2812			
Period fo	The MAILING DATE of this communication app or Reply	pears on the cover sheet with the	correspondence address -			
WHIC - Exter after - If NC - Failu Any	ORTENED STATUTORY PERIOD FOR REPLY CHEVER IS LONGER, FROM THE MAILING DANSIONS of time may be available under the provisions of 37 CFR 1.1 SIX (6) MONTHS from the mailing date of this communication. Period for reply is specified above, the maximum statutory period were to reply within the set or extended period for reply will, by statute reply received by the Office later than three months after the mailing and patent term adjustment. See 37 CFR 1.704(b).	ATE OF THIS COMMUNICATION 36(a). In no event, however, may a reply be time will apply and will expire SIX (6) MONTHS from a cause the application to become ABANDONE	N. mely filed  the mailing date of this communicated (35 U.S.C. § 133).			
Status						
1)[]	Responsive to communication(s) filed on					
	This action is <b>FINAL</b> . 2b) This					
	,	accoution as to the morit	o io			
3)☐ Since this application is in condition for allowance except for formal matters, prosecution as to the closed in accordance with the practice under Ex parte Quayle, 1935 C.D. 11, 453 O.G. 213.						
		-x parte Quayle, 1955 C.D. 11, 4	33 O.G. 213.			
Dispositi	on of Claims					
<b>4</b> )⊠	Claim(s) 1-27 is/are pending in the application.					
	4a) Of the above claim(s) <u>/2-19</u> is/are withdrawr	n from consideration.				
5)	Claim(s) is/are allowed.		ALEXANDED CHVVA			
6)⊠	Claim(s) 1-11 and 20-27 is/are rejected.		ALEXANDER GHYKA PRIMARY EXAMINER			
7)	Claim(s) is/are objected to.		A 20 12			
	Claim(s) are subject to restriction and/o on Papers	r election requirement.	Al M			
	•		Out Just	162		
	The specification is objected to by the Examine		<i>V</i> /			
10)⊠ The drawing(s) filed on <u>17 July 2003</u> is/are: a)⊠ accepted or b)□ objected to by the Examiner.						
	Applicant may not request that any objection to the					
44\	Replacement drawing sheet(s) including the correct					
11)	The oath or declaration is objected to by the Ex	caminer. Note the attached Office	e Action or form PTO-152	2.		
Priority ι	ınder 35 U.S.C. § 119					
	Acknowledgment is made of a claim for foreign All b) Some * c) None of:  1. Certified copies of the priority document		)-(d) or (f).			
	2. Certified copies of the priority document		ion No			
	3. Copies of the certified copies of the prior	• •				
	application from the International Bureau	u (PCT Rule 17.2(a)).				
* 5	See the attached detailed Office action for a list	of the certified copies not receive	ed.			
Attachmen	• •					
	e of References Cited (PTO-892)	4) Interview Summary Paper No(s)/Mail D	•			
3) Inform	e of Draftsperson's Patent Drawing Review (PTO-948) mation Disclosure Statement(s) (PTO-1449 or PTO/SB/08) r No(s)/Mail Date		Patent Application (PTO-152)			

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## **DETAILED ACTION**

The Applicants' response of March 18, 2006 has been considered and entered in the record. New Claims 20-27 have been added. The following new rejection is made in view of Applicants' amendments.

## Claim Rejections - 35 USC § 103

The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:

(a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negatived by the manner in which the invention was made.

This application currently names joint inventors. In considering patentability of the claims under 35 U.S.C. 103(a), the examiner presumes that the subject matter of the various claims was commonly owned at the time any inventions covered therein were made absent any evidence to the contrary. Applicant is advised of the obligation under 37 CFR 1.56 to point out the inventor and invention dates of each claim that was not commonly owned at the time a later invention was made in order for the examiner to consider the applicability of 35 U.S.C. 103(c) and potential 35 U.S.C. 102(e), (f) or (g) prior art under 35 U.S.C. 103(a).

Claims 1-11 and 20-27 are rejected under 35 U.S.C. 103(a) as being unpatentable over Matsumura et al (US 2002/0189545) in view of Bu et al (US 6,806,149).

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The present Claims generally require heating a substrate to be subjected to film formation, heating a wire to a wire temperature, supplying silane, ammonia and hydrogen, and forming a conformal silicon nitride film on the substrate.

Matsumura disclose heating a substrate to be subjected to film formation, heating a wire to a wire temperature, supplying silane, ammonia and hydrogen, and forming a silicon nitride film as required by present Claims 1, 5, 6, 7 and 8. See page 2, paragraphs 19- 20; page 9, paragraph 112 and page 10, paragraphs 124-126.

Matsumura further discloses a substrate temperature of 200 degrees Celcius and a wire temperature of 2000 degrees Celcius as required by present Claims 2, 3, and 9-10. See page 2, paragraph 20.

Matsumura et al differs from the presently claimed invention in that it does not disclose the formation of a conformal nitride layer.

Bu et al disclose a CVD process which uses silane, ammonia and hydrogen to form conformal silicon nitride layers. See Figures 2A – 2D, column 3, lines 5-10 and column 3, line 65 to column 4, line 30.

It would have been obvious for one of ordinary skill at the time of the invention, to use the process of Matsumura et al to form a conformal silicon nitride layer as disclosed by Bu et al, as both processes pertain to CVD processes which form silicon nitride and use hydrogen, ammonia and silane as reactants. As Bu et al disclose that CVD

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processes using the afore mentioned reactants are known in the art, the use of a known process, CVD using hydrogen, silane and ammonia as reactants, to form a known product, a conformal CVD layer, is *prima facie* obvious.

Claims 4 and 11 further require pressures of 10-50 millitorr.

Matsumura et al is relied upon as discussed above, and disclose pressures of about 0.1 PA to 100 Pa.

It would have been obvious for one of ordinary skill in the art, at the time of the invention, to arrive at the presently claimed pressures as the discovery of an optimum value of a result effective variable in a known process is ordinarily within the skill of the art. See *In re Aller*, 105 USPQ 233 (1955) and *In re Antonie*, 195 USPQ 6 (CCPA 1977). In this case the pressure would be considered a result effective variable by one of ordinary skill in the art, and the selection of the optimum parameters would be within the level of skill of one of ordinary skill in the art as simply a matter of optimization.

Claims 20-27 further require the conformal layer to have uniform thickness and exhibit 100 % step coverage.

The figures of Bu et al show uniform thickness and 100 % step coverage. See Figures 2A-2D of Bu et al.

It would have been obvious to one of ordinary skill in the art, at the time of the invention, to arrive at the presently claimed thickness and step coverage as the discovery of an optimum value of a result effective variable in a known process is

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ordinarily within the skill of the art. See *In re Aller*, 105 USPQ 233 (1955) and *In re Antonie*, 195 USPQ 6 (CCPA 1977). In this case the uniformity of the thickness and the step coverage would be considered result effective variables by one of ordinary skill in the art, and the selection of the optimum parameters would be within the level of skill of one of ordinary skill in the art as simply a matter of optimization.

## **Conclusion**

Applicant's amendment necessitated the new ground(s) of rejection presented in this Office action. Accordingly, **THIS ACTION IS MADE FINAL**. See MPEP § 706.07(a). Applicant is reminded of the extension of time policy as set forth in 37 CFR 1.136(a).

A shortened statutory period for reply to this final action is set to expire THREE MONTHS from the mailing date of this action. In the event a first reply is filed within TWO MONTHS of the mailing date of this final action and the advisory action is not mailed until after the end of the THREE-MONTH shortened statutory period, then the shortened statutory period will expire on the date the advisory action is mailed, and any extension fee pursuant to 37 CFR 1.136(a) will be calculated from the mailing date of the advisory action. In no event, however, will the statutory period for reply expire later than SIX MONTHS from the date of this final action.

Any inquiry concerning this communication or earlier communications from the examiner should be directed to Alexander G. Ghyka whose telephone number is (571)

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272-1669. The examiner can normally be reached on Monday through Friday during general business hours.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Michael Lebentritt can be reached on (571) 272-1873. The fax phone number for the organization where this application or proceeding is assigned is 571-273-8300.

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).

AGG May 22, 2006

> ALEXANDER GHYKA PRIMARY EXAMINER

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